

Lam Research Corporation Receives Best Product Award For 2300 Versys™ Silicon Etch System

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FREMONT, Calif., November 12, 2001-Lam Research Corporation (Nasdaq: LRCX), Fremont, Calif., today announced receiving Semiconductor International's Editors' Choice Best Product Award for its 2300 Versys silicon etch system. This award is based on customer nominations and honors the industry's top products for superior production performance and contributions to semiconductor manufacturing. The award was presented to Lam on November 9.

The 2300 Versys silicon etch system employs Lam's industry-leading Transformer Coupled Plasma™ technology and Clean Mode™ operation, which eliminates memory effects for repeatable processing. It is employed in all 200 mm and 300 mm silicon etch applications, including sub-100 nm processes.

"We're honored to receive this prestigious award," stated Nick Bright, vice president of global products, "and believe several factors led to this distinction. Leveraging proven etch technology on our unique 200/300 mm platform allowed numerous production successes, including achieving 300 mm process scaling of complicated processes and significant yield improvements and process stability at start-up. The platform's advanced diagnostics capability enables advanced process control and e-diagnostics, while plug and play sensor capability eases integration of future technologies to advance semiconductor manufacturing."

This press release contains certain forward-looking statements which are subject to the Safe Harbor provisions created by the Private Securities Litigation Reform Act of 1995. Such forward-looking statements include those relating to process and machine performance, yield improvements, process stability and control and the ease of integrating future technologies, among others. Such statements are based on current expectations and are subject to risks, uncertainties, and changes in condition, significance, value and effect including those risks detailed in documents filed with the Securities and Exchange Commission, and specifically the report on Form 10-K for the fiscal year ended June 24, 2001 and the Form 10-Q for the quarter ended September 23, 2001, which could cause actual results to vary from expectations. The company undertakes no obligation to update the information in this Press Release.

Lam Research Corporation is a leading supplier of wafer fabrication equipment and services to the world's semiconductor industry. Lam's common stock trades on the Nasdaq National Market under the symbol LRCX. The Company's World Wide Web address is <http://www.lamrc.com>.

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